

## Correction to Free-Standing Silicon Nanogratings for Extreme UV Rejection

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The Acknowledgments in the original manuscript were incorrect. The following is the correct version of the Acknowledgments.

## ACKNOWLEDGMENTS

The authors would like to thank Lei Chen at NIST for Pt deposition on the nanograting samples, Pran Mukherjee (currently with Akamai Technologies) for his guidance on the device fabrication, Jürgen Scheer of the University of Bern for assistance with UV experiments, and Brian Vanderelzen and Russ Clifford from the University of Michigan Lurie Nanofabrication Facility for their assistance in refining the etching processes. This research was funded under NASA PIDDP Grant NNX09AN25G.

Received: July 31, 2014
Published: August 11, 2014

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